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Top electrode-dependent retention characteristics of thin-film transistors with carbon nanotube/ $(Bi,Nd)_4Ti_3O_{12}$  structure

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## CCEPTED MANUS

Top electrode-dependent retention characteristics of thin-film transistors with carbon nanotube/ $(Bi,Nd)_4Ti_3O_{12}$  structure

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Abstract

Gradient stripe patterns of Single-Walled Carbon Nanotubes (SWCNTs) were

fabricated by using the evaporation-induced self-assembly technique. Additionally,

the nonvolatile thin-film transistors (TFTs) with SWCNTs and (Bi,Nd)<sub>4</sub>Ti<sub>3</sub>O<sub>12</sub> (BNT)

insulators were fabricated. The retention characteristics were investigated in

Pt/SWCNTs/BNT/LaNiO<sub>3</sub> and LaNiO<sub>3</sub>/SWCNTs/BNT/LaNiO<sub>3</sub> structures. Results

revealed that LaNiO<sub>3</sub>/SWCNTs/BNT/LaNiO<sub>3</sub> TFTs demonstrate larger on-state

current, wider memory window, better fatigue endurance performance and retention

characteristics, compared with Pt/SWCNTs/BNT/LaNiO<sub>3</sub> TFTs because of the

involvement of the oxide conductive electrodes. These results suggest that the

SWCNTs/BNT TFTs with LaNiO<sub>3</sub> as the electrodes are suitable for next-generation

nonvolatile memory devices and integrated circuits.

**Keywords:** Thin-film transistors (TFTs), Single-Walled Carbon Nanotube (SWCNTs),

Nonvolatile memory, Ferroelectric film

1. Introduction

Recently, Carbon Nanotubes (CNTs) ferroelectric thin-film transistors (TFTs) are

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